



PATENT APPLICATION

OLIFF & BERRIDGE, PLC
P.O. Box 19928
Alexandria, Virginia 22320
Telephone: (703) 836-6400
Facsimile: (703) 836-2787

Attorney Docket No.: 105875

AMENDMENT TRANSMITTAL

In re the Application of

Masaru MITSUI et al.
Application No.: 09/509,472

Group Art Unit: 1752
Examiner: Y. Clarke

Filed: April 21, 2000

For: PHOTOMASK BLANK, PHOTOMASK, METHODS OF MANUFACTURING THE SAME AND
METHOD OF FORMING MICROPATTERN

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

Transmitted herewith is an Amendment in the above-identified application.

- ☐ Entitlement to small entity status is hereby asserted.
☐ Small entity status of this application has been established.

The filing fee has been calculated as shown below:

| | (Column 1) | (Column 2) | (Column 3) | SMALL ENTITY | | OR | OTHER THAN A SMALL ENTITY | |
|--|----------------------------------|---------------------------------|---------------|--------------|-----------|----|---------------------------|-----------|
| | CLAIMS REMAINING AFTER AMENDMENT | HIGHEST NO. PREVIOUSLY PAID FOR | PRESENT EXTRA | RATE | ADD'L FEE | | RATE | ADD'L FEE |
| TOTAL CLAIMS | *30 MINUS | **26 | =4 | x 9 | \$ | OR | x 18 | \$72 |
| INDEP CLAIMS | *5 MINUS | ***5 | =0 | x 42 | \$ | | x 84 | \$ |
| <input type="checkbox"/> FIRST PRESENTATION OF MULTIPLE DEP. CLAIM | | | | + 140 | \$ | | +280 | \$ |
| | | | | | \$ | | | \$72 |

- * If the entry in Column 1 is less than the entry in Column 2, write "0" in Column 3.
** If the "Highest Number Previously Paid For" IN THIS SPACE is less than 20, write "20" in this space.
*** If the "Highest Number Previously Paid For" IN THIS SPACE is less than 3, write "3" in this space.

The "Highest Number Previously Paid For" in this space (Total or Independent) is the highest number found from the equivalent box in Column 1 of a prior Amendment or the number of claims originally filed.

- ☒ Check No. 127081 in the amount of \$72.00 is attached. The Director is hereby authorized to charge any other fees that may be required to complete this filing, or to credit any overpayment, to Deposit Account No. 15-0461. Two duplicate copies of this sheet are attached.

DEPOSIT ACCOUNT USE
AUTHORIZATION
Please grant any extension
necessary for entry;
Charge any fee due to our
Deposit Account No. 15-0461

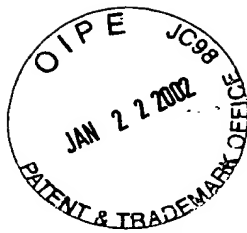
Respectfully submitted,

James A. Olf
Registration No. 27,075

Joel S. Armstrong
Registration No. 36,430

David M. Lafkas
Registration No. P-50,424

RECEIVED
JAN 30 2002
TC 1700



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Masaru MITSUI et al.

Group Art Unit: 1752

Application No.: 09/509,472

Examiner: Y. Clarke

Filed: April 21, 2000

Docket No.: 105875

For: PHOTOMASK BLANK, PHOTOMASK, METHODS OF MANUFACTURING THE SAME AND METHOD OF FORMING MICROPATTERN

AMENDMENT

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

In reply to the Office Action mailed August 22, 2001, please amend the above-identified application as follows:

IN THE SPECIFICATION:

Page 16, lines 11-23, delete current paragraph and insert therefor:

With the photomask blank 1 pertaining to Example 1 shown in Figure 1, a quartz glass substrate measuring 5 inches \times 5 inches \times 0.09 inch and whose main surface and end face had undergone precision polishing was used as the transparent substrate 2. Over this transparent substrate 2 were formed a chromium nitride (CrN) film (Cr: 80 atomic%, N: 20 atomic% (hereafter called at%); film thickness 150 Å) as a first shading film (light-shielding film, opaque film, non-transmitting film) 3, a chromium carbide (CrC) film (Cr: 94 at%, C: 6 at%; film thickness: 600 Å) as a second shading film (light-shielding film, opaque film, non-transmitting film) 4, and a chromium oxynitride (CrON) film (Cr: 30 at%, O: 45 at%, N: 25 at%; film thickness: 250 Å) as an anti-reflective film 5.

RECEIVED

JAN 30 2002

TC 1700